

CLAIMS

1. A plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein the protective layer includes carbon and silicon.
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2. A plasma display panel as claimed in claim 1, wherein a protective layer is made of magnesium oxide including silicon with 5×10^{18} atoms/cm³ to 2×10^{21} atoms/cm³, and carbon with 1×10^{18} atoms/cm³ to 2×10^{21} atoms/cm³.
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3. A plasma display panel as claimed in claim 2, wherein the number of carbon atoms is greater than that of silicon.
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4. A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein a process for forming the protective layer is a process for forming a film using a material for a protective layer, including carbon and silicon.
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5. A method of manufacturing a plasma display panel as claimed in claim 4, wherein a material for a protective layer is magnesium oxide including carbon and silicon; wherein the density of carbon ranges from 5 ppm to 1,500 ppm by weight; and wherein the density of silicon ranges from 7 ppm to 8,000 ppm by weight.
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6. A method of manufacturing a plasma display panel as claimed in claim 4, wherein a material for a protective layer is magnesium oxide including silicon carbide; and wherein the density of silicon carbide ranges from 40 ppm to 12,000 ppm by weight.

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7. A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein carbon and silicon are added in the protective layer
10 after the protective layer is formed on the dielectric layer.

8. A material for a protective layer of a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is
15 formed on the dielectric layer, wherein the material for a protective layer includes carbon and silicon.

9. A material for a protective layer of a plasma display panel as claimed in claim 8, wherein a material for a protective layer is made of magnesium oxide
20 including carbon and silicon; wherein the density of the carbon ranges from 5 ppm to 1,500 ppm by weight; and wherein the density of the silicon ranges from 7 ppm to 8,000 ppm by weight.

10. A material for a protective layer of a plasma display panel as claimed in
25 claim 8, wherein a material for a protective layer is made of magnesium oxide including silicon carbide; and wherein the density of the silicon carbide ranges from 40 ppm to 12,000 ppm by weight.